ERRATA

Critical Magnetic Field Dependence of Thermally Activated Surface Processes
[Phys. Rev. Lett. 63, 287 (1989)]

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Professor H. Suhl has pointed out that he already stressed in his work [Phys. Rev. B **11**, 2011 (1975)] the importance of the disparate time scales of heat-bath and reactant motions and gave a simple solution in the limiting case of slow substrate motion. Although we referred to his paper (Ref. 9), we should have mentioned this point explicitly to avoid the impression that previous work was oblivious of the problem of time-scale separation.

Reference 2 should read as follows: For a review of the earlier experimental work, see R. J. H. Voorhoeve, in *Magnetism and Magnetic Materials—1973,* edited by C. D. Graham and J. J. Rhyne, AIP Conference Proceedings No. 18 (American Institute of Physics, New York, 1974), p. 19.

Equation (2) should read

$$r(T,0) - r(T,H) \sim \begin{cases} H^2, & \text{for } T > T_c, \\ H^{2/\delta_1}, & \text{for } T = T_c, \\ H, & \text{for } T < T_c. \end{cases} \tag{2}$$